

TSMC-01-376



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Technology Center 2600

To: Commissioner of Patents and Trademarks  
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572  
20 McIntosh Drive  
Poughkeepsie, N.Y. 12603

Subject:

Serial No. 10/002,986 11/30/01

Burn J. Lin, Shinn-Sheng Yu,  
Bang Chein Ho

IMPROVEMENT OF CONTACT HOLE PRINTING  
BY PACKING AND UNPACKING

Grp. Art Unit:

#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56. Copies of each document is included herewith.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
mail in an envelope addressed to: Commissioner of Patents and  
Trademarks, Washington, D.C. 20231, on February 15, 2002.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

SBB DL 2/15/02

U.S. Patent 5,573,634 to Ham, "Method for Forming Contact Holes of a Semiconductor Device," discloses a double exposure contact hole method.

U.S. Patent 6,218,057 to Cirelli et al., "Lithographic Process Having Sub-Wavelength Resolution," discloses a lithographic process for contact holes using 2 masks/exposures.

U.S. Patent 6,238,850 to Bula et al., "Method of Forming Sharp Corners in a Photoresist Layer," discloses a photo method for contact holes using 2 masks/exposures.

U.S. Patent 5,308,741 to Kemp, "Lithographic Method Using Double Exposure Techniques, Mask Position Shifting and Light Phase Shifting," discloses a lithographic method using double exposures, physical mask shifting, and light phase shifting used to form masking features on a substrate masking layer.

U.S. Patent 5,897,975 to Ahn et al., "Phase Shift Mask for Formation of Contact Holes Having Micro Dimension," discusses a phase shift mask having a multi-layer structure, fabricated by forming a plurality of uniformly spaced phase shift layers on a quartz substrate, capable of forming contact holes with a micro dimension smaller than the wavelength used in the light exposure procedure.

U.S. Patent 5,795,686 to Talizawa et al., "Pattern Forming Method and Method of Manufacturing Liquied Crystal Display Device," discusses a pattern forming method of forming an overall pattern by connecting a plurality of pattern forming regions.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', with a long horizontal flourish extending to the right.

Stephen B. Ackerman,  
Reg. No. 37761